

Sheet 2 of 3

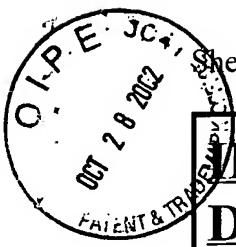
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					ATTY. DOCKET NO. F073-2	SERIAL NO. 10/081,247	
APPLICANTS Gregory A. Schwind, et al.					FILING DATE February 22, 2002	GROUP ART UNIT 2821	
U.S. PATENT DOCUMENTS							
*Examiner Initial	Cite No.	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if appropriate)
TDC	N	5,177,402	01/05/93	Howard, et al.	315	1	
TDC	O	4,818,872	04/04/89	Parker, et al.	250	309	
TDC	P	4,694,178	09/15/87	Harte	250	396	
TDC	Q	4,390,789	06/28/83	Smith, et al.	250	492,2	
TDC	R	4,126,781	11/21/78	Siegel	250	281	
FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION							
Cite No.	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
TDC S	WO 99/45565	09/10/99	WIPO	H01J37	26		
TDC T	WO 98/48443	10/29/98	WIPO	H01J37	30		
OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)							
*Examiner Initial	Cite No.						
TDC	U	"Development of Ion Sources for Ion Projection Lithography," <i>J. Vac. Sci. Technol. B</i> , Vol. 14, No. 6 (1996), pp. 3947-3950.					
TDC	V	"Energy Spread of Ion Beams Generated in Multicusp Ion Sources," <i>IEEE</i> , (1996), pp. 2542-2544.					
TDC	W	"A Compact Filament-Driven Multicusp Ion Source," <i>Nuclear Instruments and Methods in Physics Research B</i> , Vol. 119 (1996), pp. 543-548.					
TDC	X	"Beam Emittance Measurements on Multicusp Ion Sources," <i>Rev. Sci. Instrum.</i> , Vol. 67, No. 3 (1996), pp. 1249-1251.					

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U.S. PATENT DOCUMENTS							
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TDC	A	6,355,383 B1	03/12/02	Yamashita	430	5	
TDC	B	6,218,664 B1	04/17/01	Krans, et al.	250	310	
TDC	C	6,215,128 B1	04/10/01	Mankos, et al.	250	492.24	
TDC	D	6,211,518 B1	04/03/01	Richardson, et al.	250	310	
TDC	E	6,023,060	02/08/00	Chang, et al.	250	310	
TDC	F	5,981,962	11/09/99	Groves, et al.	250	492.23	
TDC	G	5,945,677	08/31/99	Leung, et al.	250	396	
TDC	H	5,834,770	11/10/98	Holkeboer, et al.	250	281	
FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION							
Cite No.	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
TDC I	WO 00/46831	08/10/00	WIPO	H01J9	18		
TDC J	WO 99/47978	09/23/99	WIPO	H01J37	317		
TDC K	WO 99/34397	07/08/99	WIPO	H01J37	28		
OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)							
*Examiner Initial	Cite No.						
TDC	L	"Ion Energy Spread and Current Measurements of the rf-driven Multicusp Ion Source," <i>Rev. Sci. Instum.</i> Vol. 68, No. 3 (1997), pp. 1398-1402.					
TDC	M	"Axial Energy Spread Measurements of an Accelerated Positive Ion Beam," <i>Nuclear Instruments and Methods in Physics Research A</i> , Vol. 385, (1997), pp. 204-208.					

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APPLICANTS Gregory A. Schwind, et al.		FILING DATE February 22, 2002	GROUP ART UNIT 2821

U.S. PATENT DOCUMENTS

*Examiner Initial	Cite No.	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if appropriate)

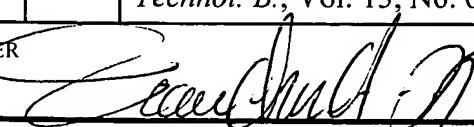
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FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

Cite No.	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No

**OTHER DOCUMENTS
(INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)**

*Examiner Initial	Cite No.	
TDC	Y	"Production of Low Energy Spread Ion Beams with Multicusp Sources," <i>Nuclear Instruments and Methods in Physics Research A</i> , Vol. 374 (1996), pp. 1-6.
TDC	Z	"Multicusp Sources for Ion Beam Lithography Applications," <i>J. Vac. Sci. Technol. B.</i> , Vol. 13, No. 6 (1995), pp. 2600-2602.

EXAMINER  DATE CONSIDERED *3/10/03*

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.